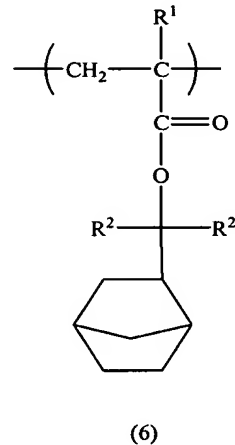
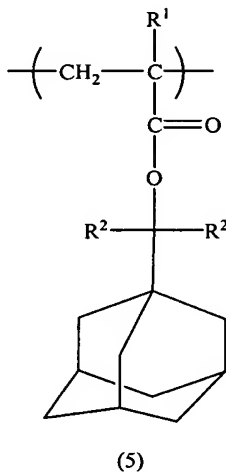
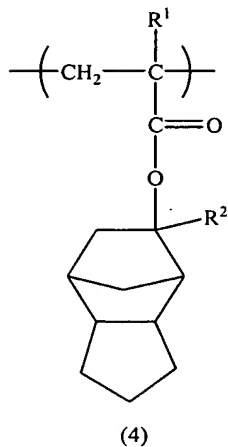
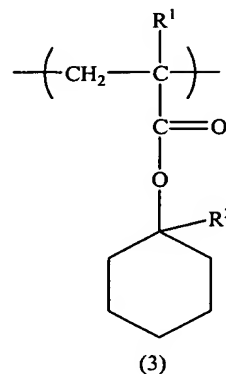
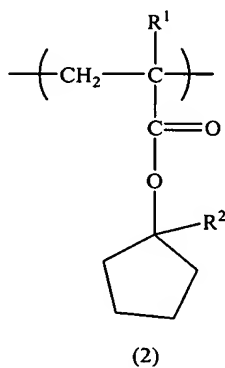
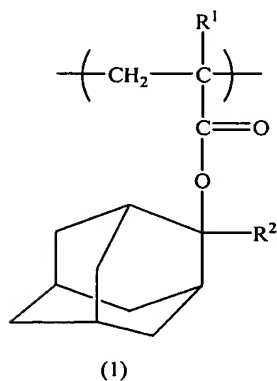


## IN THE CLAIMS

1. (Original) A radiation-sensitive resin composition comprising:

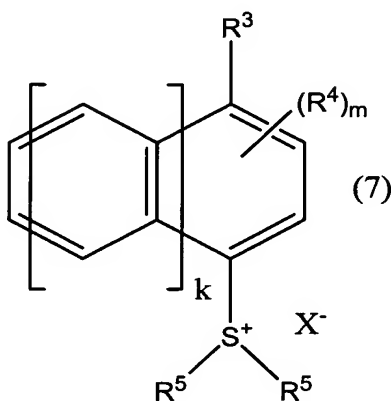
(A) a resin comprising at least two recurring units of the following formulas (1) - (6),



wherein  $R^1$  represents a hydrogen atom or methyl group and  $R^2$  represents a substituted or unsubstituted alkyl group having 1-4 carbon atoms, two or more  $R^2$  groups that may be present being either the same or different, in the total amount of 5 - 7 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

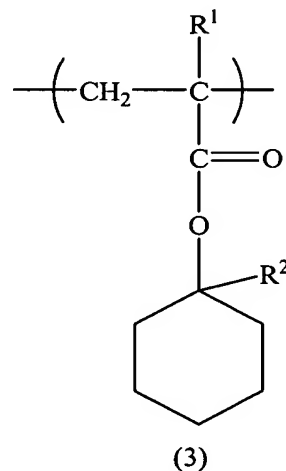
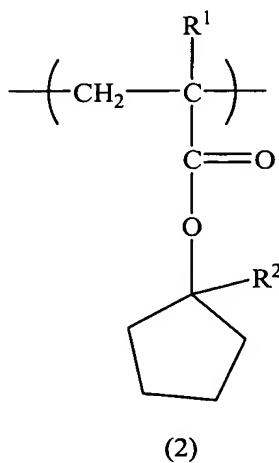
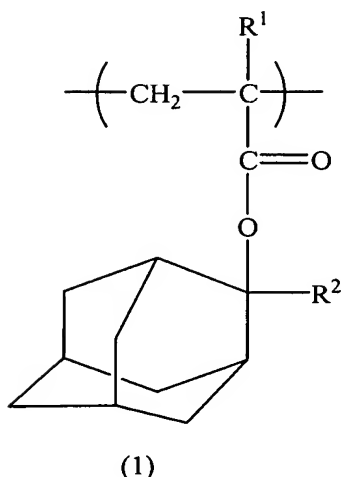
2. (Currently Amended) The radiation-sensitive resin composition according to Claim 1, wherein the photoacid generator (B) is compound shown by the formula (7),



wherein  $R^3$  represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms,  $R^4$  represents a linear or branched alkyl group having 1 - 10 carbon atoms,  $R^5$  individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two  $R^5$  groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms,  $k$  is an integer of 0 to 2,  $X^-$  represents an anion represented by the formula  $R^6C_nF_{2n}SO_3^-$  (wherein  $R^6$  represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and  $n$  is an integer of 1 to 10), and  $m$  is an integer of 0 to 10.

3. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

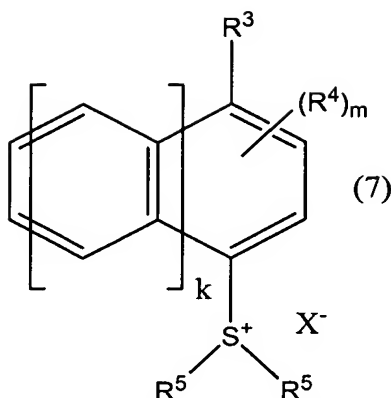
4. (Previously Presented) A radiation-sensitive resin composition comprising:  
a resin comprising at least two recurring units of the following formulas (1) - (3),



wherein  $R^1$  represents a hydrogen atom or methyl group and  $R^2$  represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, two or more  $R^2$  groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

5. (Currently Amended) The radiation-sensitive resin composition according to Claim 4, wherein the photoacid generator (B) is the compound shown by the formula (7),

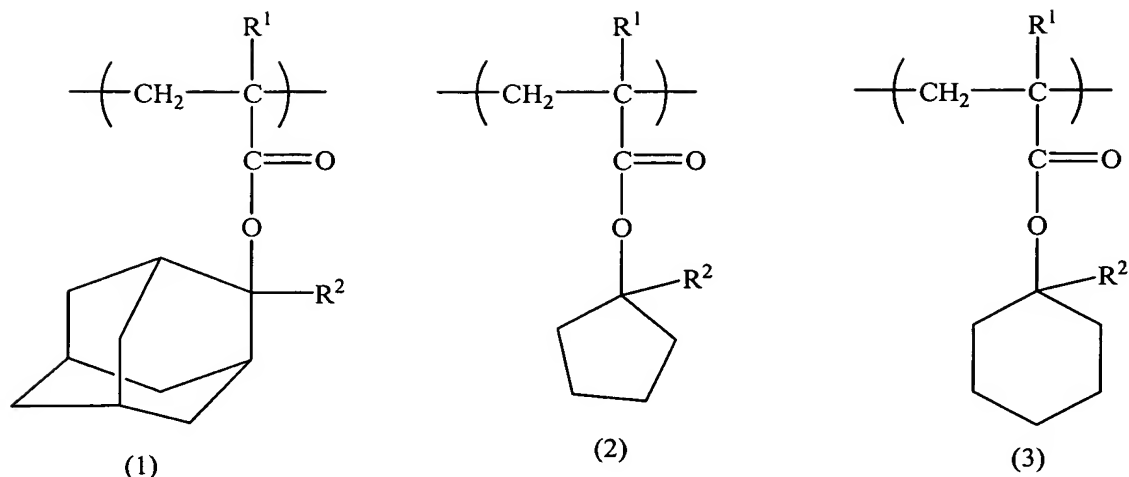


wherein  $R^3$  represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms,  $R^4$  represents a linear or branched alkyl group having 1 - 10 carbon atoms,  $R^5$  individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two  $R^5$  groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms,  $k$  is an integer of 0 to 2,  $X^-$  represents an anion represented by the formula  $R^6C_nF_{2n}SO_3^-$  (wherein  $R^6$  represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and  $n$  is an integer of 1 to 10), and  $m$  is an integer of 0 to 10.

6. (Previously Presented) The radiation-sensitive composition according to Claim 4, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

7. (Previously Presented) A radiation-sensitive resin composition comprising,

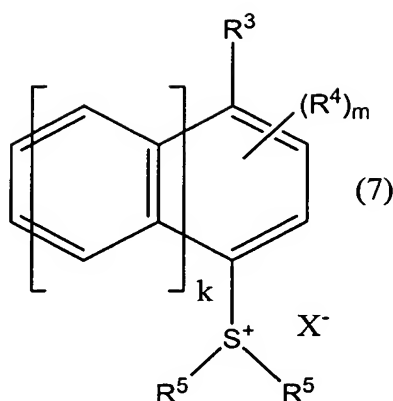
(A) a resin comprising at least one recurring unit of the following formulas (1) - (3),



wherein  $R^1$  represents a hydrogen atom or methyl group and  $R^2$  is a methyl group, and at least one recurring unit of the above formulas (1) - (3), wherein  $R^1$  represents a hydrogen atom or methyl group and  $R^2$  represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, excluding a methyl group, two or more  $R^2$  groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

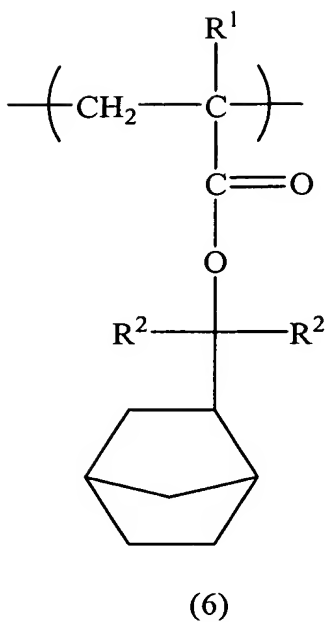
8. (Currently Amended) The radiation-sensitive resin composition according to Claim 7, wherein the photoacid generator (B) is the compound shown by the formula (7),



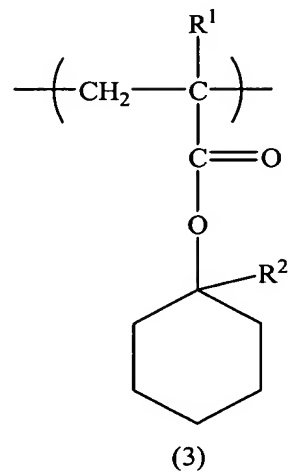
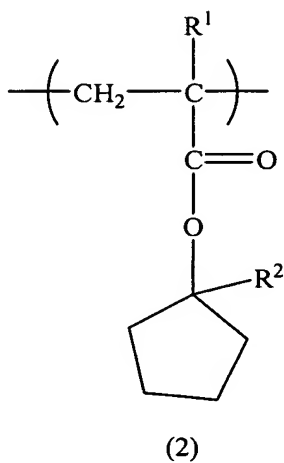
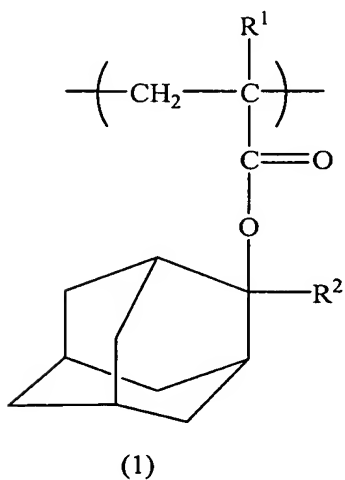
wherein  $R^3$  represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms,  $R^4$  represents a linear or branched alkyl group having 1 - 10 carbon atoms,  $R^5$  individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two  $R^5$  groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms,  $k$  is an integer of 0 to 2,  $X^-$  represents an anion represented by the formula  $R^6C_nF_{2n}SO_3^-$  (wherein  $R^6$  represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and  $n$  is an integer of 1 to 10), and  $m$  is an integer of 0 to 10.

9. (Previously Presented) The radiation-sensitive resin composition according to Claim 7, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

10. (Previously Presented) A radiation-sensitive resin composition comprising,  
(A) a resin comprising at least one recurring unit of the following formula (6),



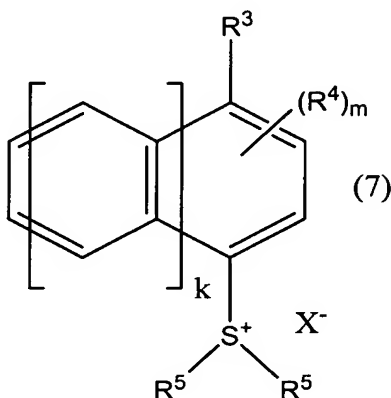
wherein  $\text{R}^2$  is a methyl group, and at least one recurring unit selected from the group consisting of the recurring units of the formulas (1) - (3),



wherein  $\text{R}^1$  represents a hydrogen atom or methyl group and  $\text{R}^2$  is a methyl group, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

11. (Currently Amended) The radiation-sensitive resin composition according to Claim 10, wherein the photoacid generator (B) is the compound shown by the formula (7),



wherein  $R^3$  represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms,  $R^4$  represents a linear or branched alkyl group having 1 - 10 carbon atoms,  $R^5$  individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two  $R^5$  groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms,  $k$  is an integer of 0 to 2,  $X^-$  represents an anion represented by the formula  $R^6C_nF_{2n}SO_3^-$  (wherein  $R^6$  represents a fluoroine atom or substituted or unsubstituted monovalent hydrocarbon group and  $n$  is an integer of 1 to 10), and  $m$  is an integer of 0 to 10.

12. (Previously Presented) The radiation-sensitive resin composition according to Claim 10, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.